

Title (en)  
PROCESS AND APPARATUS FOR THE ELECTROLYTICAL DEPOSITION OF METALS

Publication  
**EP 0142010 B1 19871223 (DE)**

Application  
**EP 84111959 A 19841005**

Priority  
DE 3340732 A 19831110

Abstract (en)  
[origin: ES8601338A1] The strip enters the electrolyte (in 8) in vertically downward direction and, after passing around a roller (10), leaves the electrolyte (in 12) in vertically upward direction. A high flow velocity of the electrolyte is maintained relative to the strip and to the anodes (9,11). - The electrolyte is caused to move in counterflow relative to the strip transport direction over the entire strip length (a+a) passing between the anodes (9,11). The electrolyte flow may be produced by applying a pressure differential, e.g. by feeding the electrolyte into the upper end of the strip run-out section (12) which is lower (delta h) than the upper end (overflow) of the run-in section (8) communicating therewith.  
[origin: ES8601338A1] The strip enters the electrolyte (in 8) in vertically downward direction and, after passing around a roller (10), leaves the electrolyte (in 12) in vertically upward direction. A high flow velocity of the electrolyte is maintained relative to the strip and to the anodes (9,11). - The electrolyte is caused to move in counterflow relative to the strip transport direction over the entire strip length (a+a) passing between the anodes (9,11). The electrolyte flow may be produced by applying a pressure differential, e.g. by feeding the electrolyte into the upper end of the strip run-out section (12) which is lower (delta h) than the upper end (overflow) of the run-in section (8) communicating therewith.

IPC 1-7  
**C25D 7/06; C25D 5/08**

IPC 8 full level  
**C25D 5/08** (2006.01); **C25D 7/06** (2006.01)

CPC (source: EP KR US)  
**C25D 7/06** (2013.01 - KR); **C25D 7/0628** (2013.01 - EP US)

Citation (examination)  
PATENT ABSTRACTS OF JAPAN, unexamined applications, C field, vol. 6, no. 3, January 9, 1982, THE PATENT OFFICE JAPANESE GOVERNMENT, page 83 C 86

Cited by  
DE4442388A1; DE4442388C2; US6395163B1; EP0713932A1; US9878044B2; US11510988B2

Designated contracting state (EPC)  
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**EP 0142010 A1 19850522; EP 0142010 B1 19871223**; AT E31560 T1 19880115; AU 3529684 A 19850516; CA 1251415 A 19890321; DE 3468239 D1 19880204; DK 529384 A 19850511; DK 529384 D0 19841107; ES 537508 A0 19851016; ES 8601338 A1 19851016; JP S60114593 A 19850621; KR 850004134 A 19850701; KR 920000247 B1 19920110; NO 844498 L 19850513; US 4634504 A 19870106

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**EP 84111959 A 19841005**; AT 84111959 T 19841005; AU 3529684 A 19841109; CA 467521 A 19841109; DE 3468239 T 19841005; DK 529384 A 19841107; ES 537508 A 19841108; JP 23051384 A 19841102; KR 840006948 A 19841106; NO 844498 A 19841109; US 67040884 A 19841109